

Jose-Luis Andujar

List of Publications by Year in descending order

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69
papers

1,502
citations

304368

22
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360668

35
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70
all docs

70
docs citations

70
times ranked

1197
citing authors

#	ARTICLE	IF	CITATIONS
1	Preparation of tetrahedral amorphous carbon films by filtered cathodic vacuum arc deposition. <i>Diamond and Related Materials</i> , 2000, 9, 663-667.	1.8	154
2	Structural effects of nanocomposite films of amorphous carbon and metal deposited by pulsed-DC reactive magnetron sputtering. <i>Diamond and Related Materials</i> , 2007, 16, 1828-1834.	1.8	72
3	Insitu spectroellipsometric study of the nucleation and growth of amorphous silicon. <i>Journal of Applied Physics</i> , 1990, 68, 2752-2759.	1.1	68
4	Preparation of metal (W, Mo, Nb, Ti) containing a-C:H films by reactive magnetron sputtering. <i>Surface and Coatings Technology</i> , 2004, 177-178, 409-414.	2.2	67
5	Structure of diamond-like carbon films containing transition metals deposited by reactive magnetron sputtering. <i>Diamond and Related Materials</i> , 2005, 14, 1103-1107.	1.8	63
6	Study of the mechanical properties of tetrahedral amorphous carbon films by nanoindentation and nanowear measurements. <i>Diamond and Related Materials</i> , 2001, 10, 145-152.	1.8	61
7	Influence of pressure and radio frequency power on deposition rate and structural properties of hydrogenated amorphous silicon thin films prepared by plasma deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1991, 9, 2216-2221.	0.9	52
8	Characterization of DLC films obtained at room temperature by pulsed-dc PECVD. <i>Diamond and Related Materials</i> , 2004, 13, 1494-1499.	1.8	50
9	Growth of hydrogenated amorphous carbon films in pulsed d.c. methane discharges. <i>Diamond and Related Materials</i> , 2003, 12, 98-104.	1.8	49
10	Ellipsometric study of a-Si:H thin films deposited by square wave modulated rf glow discharge. <i>Journal of Applied Physics</i> , 1991, 69, 632-638.	1.1	39
11	Effects of gas pressure and r.f. power on the growth and properties of magnetron sputter deposited amorphous carbon thin films. <i>Diamond and Related Materials</i> , 2002, 11, 1005-1009.	1.8	37
12	Real time controlled rf reactor for deposition of a-Si:H thin films. <i>Vacuum</i> , 1989, 39, 795-798.	1.6	34
13	Effects of plasma processing on the microstructural properties of silicon powders. <i>Plasma Sources Science and Technology</i> , 1994, 3, 348-354.	1.3	33
14	In situ optical characterizations for rf plasma deposited a-Si: H thin films. <i>Vacuum</i> , 1989, 39, 785-787.	1.6	30
15	Plasma-enhanced chemical vapor deposition of boron nitride thin films from B ₂ H ₆ -H ₂ -NH ₃ and B ₂ H ₆ -N ₂ gas mixtures. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1998, 16, 578-586.	0.9	28
16	Spontaneous formation of nanometric multilayers of metal-carbon films by up-hill diffusion during growth. <i>Applied Physics Letters</i> , 2005, 87, 2131-2137.	1.5	28
17	Diamond like carbon films deposited from graphite target by asymmetric bipolar pulsed-DC magnetron sputtering. <i>Diamond and Related Materials</i> , 2007, 16, 1286-1290.	1.8	28
18	Effects of environmental conditions on fluorinated diamond-like carbon tribology. <i>Diamond and Related Materials</i> , 2009, 18, 923-926.	1.8	28

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19	Spectroscopic ellipsometric study of tetrahedral amorphous carbon films: optical properties and modelling. <i>Diamond and Related Materials</i> , 2001, 10, 1132-1136.	1.8	27
20	Composition and morphology of metal-containing diamond-like carbon films obtained by reactive magnetron sputtering. <i>Thin Solid Films</i> , 2005, 482, 293-298.	0.8	27
21	Plasma parameters of pulsed-dc discharges in methane used to deposit diamondlike carbon films. <i>Journal of Applied Physics</i> , 2009, 106, 033302.	1.1	25
22	Time-resolved electrical measurements of a pulsed-dc methane discharge used in diamond-like carbon films production. <i>Thin Solid Films</i> , 2005, 482, 172-176.	0.8	24
23	Effect of a Balanced Concentration of Hydrogen on Graphene CVD Growth. <i>Journal of Nanomaterials</i> , 2016, 2016, 1-10.	1.5	24
24	Fluorinated DLC deposited by pulsed-DC plasma for antisticking surface applications. <i>Diamond and Related Materials</i> , 2008, 17, 1728-1732.	1.8	22
25	Comparative study of metal/amorphous-carbon multilayer structures produced by magnetron sputtering. <i>Diamond and Related Materials</i> , 2003, 12, 1008-1012.	1.8	21
26	Super-Capacitive Performance of Manganese Dioxide/Graphene Nano-Walls Electrodes Deposited on Stainless Steel Current Collectors. <i>Materials</i> , 2019, 12, 483.	1.3	21
27	Hard coatings for mechanical applications. <i>Vacuum</i> , 2002, 64, 181-190.	1.6	16
28	Characterization of diamond-like carbon thin films produced by pulsed-DC low pressure plasma monitored by a Langmuir probe in time-resolved mode. <i>Diamond and Related Materials</i> , 2005, 14, 1062-1066.	1.8	16
29	Laser-induced nanostructuring of vertically aligned carbon nanotubes coated with nickel oxide nanoparticles. <i>Journal of Materials Science</i> , 2017, 52, 4002-4015.	1.7	16
30	Homogeneous Fe ₂ O ₃ coatings on carbon nanotube structures for supercapacitors. <i>Dalton Transactions</i> , 2020, 49, 4136-4145.	1.6	16
31	Properties of amorphous silicon thin films grown in square wave modulated silane rf discharges. <i>Journal of Applied Physics</i> , 1992, 71, 1546-1548.	1.1	15
32	Microstructure of highly oriented, hexagonal, boron nitride thin films grown on crystalline silicon by radio frequency plasma-assisted chemical vapor deposition. <i>Journal of Applied Physics</i> , 1996, 80, 6553-6555.	1.1	14
33	Effect of substrate temperature on deposition rate of rf plasma-deposited hydrogenated amorphous silicon thin films. <i>Journal of Applied Physics</i> , 1991, 69, 3757-3759.	1.1	13
34	Optical and structural characterization of hydrogenated amorphous silicon carbide thin films prepared by r.f. plasma chemical vapour deposition. <i>Diamond and Related Materials</i> , 1995, 4, 1205-1209.	1.8	13
35	Accurate electrical measurements for in situ diagnosis of RF discharges in plasma CVD processes. <i>Vacuum</i> , 1999, 53, 1-5.	1.6	13
36	Structural and optical properties of diamond like thin films deposited by asymmetric bipolar pulsed-DC reactive magnetron sputtering. <i>Surface and Coatings Technology</i> , 2008, 202, 2354-2357.	2.2	13

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37	Optical study of boron nitride thin films prepared by plasma-enhanced chemical vapor deposition. <i>Diamond and Related Materials</i> , 1997, 6, 1550-1554.	1.8	12
38	Nanopowder of silicon nitride produced in radio frequency modulated glow discharges from SiH ₄ and NH ₃ . <i>Surface and Coatings Technology</i> , 1998, 100-101, 55-58.	2.2	12
39	Nanoparticles of SiC _x N _{1-x} from low temperature RF plasmas: selective size, composition and structure. <i>Applied Surface Science</i> , 1999, 144-145, 702-707.	3.1	12
40	Error minimization method for spectroscopic and phase-modulated ellipsometric measurements on highly transparent thin films. <i>Journal of the Optical Society of America A: Optics and Image Science, and Vision</i> , 1993, 10, 713.	0.8	11
41	Optical and structural characterization of boron nitride thin films. <i>Diamond and Related Materials</i> , 1995, 4, 657-660.	1.8	11
42	Growth of diamond films on boron nitride thin films by bias-assisted hot filament chemical vapor deposition. <i>Applied Physics Letters</i> , 1997, 70, 1682-1684.	1.5	11
43	Optical emission spectroscopy of rf glow discharges of methane-silane mixtures. <i>Thin Solid Films</i> , 1998, 317, 120-123.	0.8	11
44	Low friction and protective diamond-like carbon coatings deposited by asymmetric bipolar pulsed plasma. <i>Diamond and Related Materials</i> , 2009, 18, 1035-1038.	1.8	11
45	Ion energy distributions in bipolar pulsed-dc discharges of methane measured at the biased cathode. <i>Plasma Sources Science and Technology</i> , 2011, 20, 015006.	1.3	11
46	Plasma-deposited silicon nitride films with low hydrogen content for amorphous silicon thin-film transistors application. <i>Sensors and Actuators A: Physical</i> , 1993, 37-38, 333-336.	2.0	10
47	Spectral ellipsometric and compositional characterization of hydrogenated amorphous silicon carbide thin films. <i>Diamond and Related Materials</i> , 1995, 4, 702-705.	1.8	10
48	Growth kinetics of nanometric dendrites in metal-carbon thin films. <i>Acta Materialia</i> , 2009, 57, 4948-4956.	3.8	10
49	Surface structuring of diamond-like carbon films by colloidal lithography with silica sub-micron particles. <i>Diamond and Related Materials</i> , 2010, 19, 1124-1130.	1.8	10
50	Optical, vibrational and compositional study of amorphous silicon oxynitride thin films grown by an RF plasma using N ₂ O + SiH ₄ gas mixtures. <i>Applied Surface Science</i> , 1993, 70-71, 695-700.	3.1	9
51	Carbon nitride thin-films deposited from coupled r.f.-magnetron sputtering and ion beam-assisted processes. <i>Diamond and Related Materials</i> , 2001, 10, 1175-1178.	1.8	9
52	Effect of hydrogen dilution on the growth of hydrogenated amorphous silicon studied by in-situ phase-modulated ellipsometry. <i>Thin Solid Films</i> , 1993, 228, 109-112.	0.8	8
53	Effects of thermal and laser annealing on silicon carbide nanopowder produced in radio frequency glow discharge. <i>Diamond and Related Materials</i> , 1997, 6, 1559-1563.	1.8	8
54	Optical and electrical properties of a-Si _x Ny:H films prepared by rf plasma using N ₂ +SiH ₄ gas mixtures. <i>Journal of Non-Crystalline Solids</i> , 1991, 137-138, 895-898.	1.5	7

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55	Effects of deposition temperature on properties of r.f. glow discharge amorphous silicon thin films. <i>Thin Solid Films</i> , 1991, 205, 140-145.	0.8	7
56	Properties of W/a-C nanometric multilayers produced by RF-pulsed magnetron sputtering. <i>Diamond and Related Materials</i> , 2002, 11, 1000-1004.	1.8	7
57	Visible and infrared ellipsometry applied to the study of metal-containing diamond-like carbon coatings. <i>Thin Solid Films</i> , 2004, 455-456, 370-375.	0.8	7
58	Kinetic model of thin film growth by vapor deposition. <i>European Physical Journal D</i> , 2005, 35, 505-511.	0.6	7
59	Properties of a-C:H films deposited from a methane electron cyclotron wave resonant plasma. <i>Current Applied Physics</i> , 2003, 3, 433-437.	1.1	5
60	In situ fast ellipsometric analysis of repetitive surface phenomena. <i>Review of Scientific Instruments</i> , 1997, 68, 3135-3139.	0.6	4
61	Microstructural and mechanical properties of nanometric-multilayered a-CN/a-C/a-C/a-CN coatings deposited by rf-magnetron sputtering and nitrogen ion-beam bombardment. <i>Diamond and Related Materials</i> , 2001, 10, 952-955.	1.8	4
62	Laser-driven coating of vertically aligned carbon nanotubes with manganese oxide from metal organic precursors for energy storage. <i>Nanotechnology</i> , 2017, 28, 395405.	1.3	4
63	Glow discharge deposited a-Si:H,Al thin films. <i>Solar Energy Materials and Solar Cells</i> , 1987, 15, 167-173.	0.4	3
64	Surface roughness evolution in the growth of a-Si: H thin films studied by ellipsometry. <i>Surface Science</i> , 1991, 251-252, 191-194.	0.8	3
65	Diffusion and effusion analysis of hydrogen in undoped hydrogenated amorphous silicon thin films. <i>Applied Surface Science</i> , 1993, 70-71, 680-685.	3.1	3
66	In situ real-time ellipsometric study of the growth of r.f. plasma deposited amorphous hydrogenated silicon oxynitride thin films. <i>Thin Solid Films</i> , 1993, 228, 137-140.	0.8	3
67	Effects of r.f. power on optical and electrical properties of plasma-deposited hydrogenated amorphous silicon thin films. <i>Sensors and Actuators A: Physical</i> , 1993, 37-38, 733-736.	2.0	2
68	Application of infrared Fourier transform phase-modulated ellipsometry to the characterization of silicon-based amorphous thin films. <i>Thin Solid Films</i> , 1998, 313-314, 671-675.	0.8	2
69	Study of thin films of transparent electronic materials by phase-modulated spectroellipsometry. <i>Thin Solid Films</i> , 1993, 233, 223-226.	0.8	1